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Professor Allan Matthews,
Editor in Chief: Surface & Coatings Technology

9th June 2016

Dear Allan,

Find as follows requested “Corrigendum”, referring to following published paper:-

Enhanced hollow cathode plasma source for assisted low pressure electron beam deposition processes. / Child, David; Gibson, Desmond; Placido, Frank; Waddell, Ewan.

The Authors regret that the Young’s Modulus and Hardness measurements were not properly acknowledged and the passage referring to Fig 8 (page 109) is inaccurate with regard to the measurement method.

As such following together with affiliation to be added as an author (page 105): “John Kavanagh, Research Centre in Surface Engineering, Department of Materials Science and Engineering, The University of Sheffield, Sheffield S1 3JD, UK”.

Also paragraph 6 in section 3.4 page 109 as follows;

“The same samples were measured using a Hysitron SN5 060-040 triboscope set to 40nm depth to minimise substrate effects with the reduced Young’s modulus and hardness calculated. Fig.8 shows the corresponding reduced Young’s modulus and hardness.” to be replaced with following;

“A Hysitron triboscope was used to measure the same samples with the applied force chosen to keep indentation depth at approximately 10% of film thickness to minimise substrate contributions. Fig 8 shows the calculated reduced Young’s modulus and hardness.”

In addition Fig 8 caption, section 3.4 page 109, “Reduced Young’s modulus Er and hardness H calculated from nanoindentations at 500µm with indentation depth at 10% of film thickness ; 4 indentations per measurement” should read “Reduced Young’s modulus Er and hardness H calculated from nanoindentations at 500µN”

The Authors would like to apologise for any inconvenience caused.

Yours sincerely,

Professor Des Gibson